

## EAST Search History

Ref #	Hits	Search Query	DBs	Default Operator	Plurals	Time Stamp
L5	9.	(implant\$3 and active and ((lightly adj doped adj drain) or LDD) and nitride and (gate\$1 adj (insulat\$3 or dielectric)) and gate\$1 and polysilicon and ((sidewall\$1 or spacer\$1) same etch\$3 same nitride same oxide)).clm.	US-PGPUB; USPAT; USOCR; EPO; JPO; IBM_TDB	OR	ON	2006/10/29 15:04